

Title (en)
Vacuum plasma generator

Title (de)
Vakuumpasmagenerator

Title (fr)
Générateur de plasma sous vide

Publication
EP 1701376 B1 20061108 (DE)

Application
EP 05005248 A 20050310

Priority
EP 05005248 A 20050310

Abstract (en)
[origin: EP1701376A1] A vacuum plasma generator (1) comprises a mains connection (2) for connection to a voltage supply network; and a mains rectifier (3) that is connected to a first converter (4) that generates an intermediate circuit voltage (5), a first radio frequency (RF) signal generator (6) that generates a first signal of a basic frequency and of a first phase position, a second RF signal generator (7) that generates a second signal of the basic frequency and of a second phase position, and 3 dB coupler (13) that couples the first and the second signal and generates an output signal. An independent claim is also included for a method of treating workpieces in a vacuum chamber, comprising: (A) receiving a mains voltage from a voltage supply network; (B) generating intermediate circuit voltage; (C) generating a first RF signal of a basic frequency, and of a first phase position, from the intermediate circuit voltage; (D) generating a second RF signal of the basic frequency, and of a second phase position, from the intermediate circuit voltage; and (E) coupling the first and the second signal and generating an output signal for the vacuum chamber using a 3 dB coupler.

IPC 8 full level
H01J 37/32 (2006.01)

CPC (source: EP KR US)
H01J 37/32 (2013.01 - KR); **H01J 37/32082** (2013.01 - EP US); **H01J 37/32174** (2013.01 - EP US); **H05H 1/30** (2013.01 - KR); **H03H 7/40** (2013.01 - EP US)

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